

WEST Search History

DATE: Wednesday, July 27, 2005

| Hide? | <u>Set</u> <u>Name</u> | <u>Query</u> | <u>Hit</u> <u>Count</u> |
|--------------------------|---------------------------|---|----------------------------|
| | | <i>DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i> | |
| <input type="checkbox"/> | L26 | 91062128 | 1 |
| | | <i>DB=JPAB; PLUR=YES; OP=ADJ</i> | |
| <input type="checkbox"/> | L25 | JP-91062128-B.did. | 0 |
| | | <i>DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i> | |
| <input type="checkbox"/> | L24 | 63015710 | 2 |
| <input type="checkbox"/> | L23 | 6315710 | 2 |
| | | <i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i> | |
| <input type="checkbox"/> | L22 | L20 and ((substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5) with (UV or ultraviolet) with ((ozone or 'O.sub.3'))) | 7 |
| <input type="checkbox"/> | L21 | L20 and ((substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5) with (UV or ultraviolet) with ((ozone or 'O.sub.3') adj7 (water or liquid or solution))) | 0 |
| <input type="checkbox"/> | L20 | dainippon screen | 17027 |
| | | <i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i> | |
| <input type="checkbox"/> | L19 | L18 and l8 | 17 |
| <input type="checkbox"/> | L18 | 134/902,56R,58R,18,1,33;438/905,906.ccls. | 6768 |
| | | <i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i> | |
| <input type="checkbox"/> | L17 | (substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5) with (UV or ultraviolet) with ((ozone or 'O.sub.3') adj7 (water or liquid or solution)) | 29 |
| <input type="checkbox"/> | L16 | L15 with (rotat\$3 or spin\$3) | 10 |
| <input type="checkbox"/> | L15 | (substrate or wafer or semiconductor or workpiece) with (clean\$3 or treat\$3 or wash\$3) with (UV or ultraviolet) with ((ozone or 'O.sub.3') adj7 (water or liquid or solution)) | 69 |
| | | <i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i> | |
| <input type="checkbox"/> | L14 | 19 same ((substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5)) | 1 |
| <input type="checkbox"/> | L13 | 19 with (substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5) | 1 |
| | | <i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i> | |
| <input type="checkbox"/> | L12 | 19 with (substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5) | 0 |
| <input type="checkbox"/> | L11 | L10 and l8 | 6 |
| <input type="checkbox"/> | L10 | 134/902,56R,58R.ccls. | 3061 |

DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

☐ L9 (UV or ultraviolet) with (control\$5 or switch\$3) with power 436

DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ

☐ L8 (UV or ultraviolet) with (control\$5 or switch\$3) with power 1099

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

☐ L7 (UV or ultraviolet) with (control\$5 or switch\$3) with power 1535

☐ L6 L5 same (ozone or 'O.sub.3') 21

☐ L5 ((substrate or wafer or semiconductor or workpiece) with (clean\$3 or treat\$3 or wash\$3)) same ((UV or ultraviolet) with (control\$5 or switch\$3)) 194

☐ L4 L2 same (ozone or 'O.sub.3') 17

☐ L3 L2 with (ozone or 'O.sub.3') 12

☐ L2 (substrate or wafer or semiconductor or workpiece) with (clean\$3 or treat\$3 or wash\$3) with (UV or ultraviolet) with (control\$5 or switch\$3) 98

☐ L1 (substrate or wafer or semiconductor or workpiece) with (clean\$3 or treat\$3 or wash\$3) with ((UV or ultraviolet) adj 10 (control\$5 or switch\$3)) 0

END OF SEARCH HISTORY